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Filed : September 11, 2000

**VERSION WITH MARKINGS TO SHOW CHANGES MADE**

**In the Claims:**

Claims 1, 2, 7, 11, 14-17, 19, 22 57, 61 and 62 have been amended as follows:

1. (AMENDED) A load lock that defines at least partially a first chamber and an auxiliary chamber, said load lock comprising:

a first port and a second port, said first and second ports for moving a wafer into and out of said load lock;

an elevator plate including a wafer carrier that is adapted for receiving a plurality of wafers and is attached to said elevator plate; and

said wafer carrier and said elevator plate being moveable between a first position where said wafer carrier is in said first chamber and a second position where said wafer carrier is in said auxiliary chamber and said elevator plate substantially seals said auxiliary chamber from said first chamber.

2. (AMENDED) A load lock as set forth in Claim 1, wherein said load lock is formed at least in part by a first housing portion and an auxiliary housing portion that is removably coupled to said first housing portion.

7. (AMENDED) A load lock that defines at least partially a first chamber and an auxiliary chamber, said load lock comprising:

a first port and a second port, said first and second ports for moving a wafer into and out of said load lock;

an elevator plate including a wafer carrier that is adapted for receiving a plurality of wafers; and

said wafer carrier being moveable between a first position where said wafer carrier is in said first chamber and a second position where said wafer carrier is in said auxiliary chamber and said elevator plate substantially seals said auxiliary chamber from said first chamber, [A load lock port as set forth in Claim 1,] wherein said first and second ports open into said first chamber.

11. (AMENDED) A load lock as set forth in Claim 10, wherein said load lock comprises a first housing portion and an auxiliary housing portion, said first port being located

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on said first housing portion and said second port being located on said auxiliary housing portion.

14. (AMENDED) A load lock as set forth in Claim 1, wherein said first port is configured to receive said wafer carrier and said wafer carrier and said elevator plate being moveable between an outside position where said wafer carrier is outside said load lock and an inside position wherein said wafer carrier is inside said load lock.

15. (AMENDED) A load lock that defines at least partially a first chamber and an auxiliary chamber, said load lock comprising:

a first port and a second port, said first and second ports for moving a wafer into and out of said load lock;

an elevator plate including a wafer carrier that is adapted for receiving a plurality of wafers; and

said wafer carrier being moveable between a first position where said wafer carrier is in said first chamber and a second position where said wafer carrier is in said auxiliary chamber and said elevator plate substantially seals said auxiliary chamber from said first chamber wherein said first port is configured to receive said wafer carrier and said wafer carrier being moveable between an outside position where said wafer carrier is outside said load lock and an inside position wherein said wafer carrier is inside said load lock, [A load lock as set forth in Claim 14,] wherein said load lock further includes a second elevator plate configured such that said second elevator plate substantially closes said first port when said wafer carrier is in said inside position.

16. (AMENDED) A load lock as set forth in Claim 15 [14], wherein said second port opens into said auxiliary chamber.

17. (AMENDED) A load lock as set forth in Claim 15 [14], wherein said second port opens into said first chamber.

19. (AMENDED) A load lock that defines at least partially a first chamber and an auxiliary chamber, said load lock comprising:

a first port and a second port, said first and second ports for moving a wafer into and out of said load lock;

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an elevator plate including a wafer carrier that is adapted for receiving a plurality of wafers; and

said wafer carrier being moveable between a first position where said wafer carrier is in said first chamber and a second position where said wafer carrier is in said auxiliary chamber and said elevator plate substantially seals said auxiliary chamber from said first chamber, wherein said auxiliary chamber includes inner walls that are adapted to withstand an auxiliary fluid and [A load lock as set forth in Claim 18,] wherein said auxiliary fluid comprises HF vapor. → Does not wait A.P. 2114

22. (AMENDED) A load lock that defines at least partially a first chamber and an auxiliary chamber, said load lock comprising:

a first port and a second port, said first and second ports for moving a wafer into and out of said load lock;

an elevator plate including a wafer carrier that is adapted for receiving a plurality of wafers; and

said wafer carrier being moveable between a first position where said wafer carrier is in said first chamber and a second position where said wafer carrier is in said auxiliary chamber and said elevator plate substantially seals said auxiliary chamber from said first chamber, wherein said load lock further includes heating elements and [A load lock as set forth in Claim 20,] wherein said heating elements are located upon the elevator plate.

57. (AMENDED) A system for processing substrates, comprising  
a load lock chamber including a lower portion having a first inner width and an upper portion attached to the lower portion and having a narrower second inner width, the chamber including a first port and a second port, each of the ports sized to pass substrates therethrough, the load lock chamber further comprising a moveable platform configured to support at least one substrate thereon and sized to have a width less than the first inner width and greater than the second inner width to enable selectively sealing the upper portion with the at least one substrate supported thereon;

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an auxiliary processing system selectively communicating with an opening in the upper chamber;

a substrate handling chamber selectively communicating with the load lock chamber through the first port; and

at least one process chamber selectively communicating with the substrate handling chamber.

61. (AMENDED) A system for processing substrates, comprising  
a load lock chamber including a lower portion having a first inner width and an upper portion having a narrower second inner width, the chamber including a first port and a second port, each of the ports sized to pass substrates therethrough, the load lock chamber further comprising a moveable platform configured to support at least one substrate thereon and sized to have a width less than the first inner width and greater than the second inner width to enable selectively sealing the upper portion with the at least one substrate supported thereon;

a substrate handling chamber selectively communicating with the load lock chamber through the first port; and

at least one process chamber selectively communicating with the substrate handling chamber, [The system of Claim 57,] wherein the first port is located in the upper portion.

62. (AMENDED) A system for processing substrates, comprising  
a load lock chamber including a lower portion having a first inner width and an upper portion having a narrower second inner width, the chamber including a first port and a second port, each of the ports sized to pass substrates therethrough, the load lock chamber further comprising a moveable platform configured to support at least one substrate thereon and sized to have a width less than the first inner width and greater than the second inner width to enable selectively sealing the upper portion with the at least one substrate supported thereon;

a substrate handling chamber selectively communicating with the load lock chamber through the first port; and

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at least one process chamber selectively communicating with the substrate handling chamber, [The system of Claim 57,] wherein the upper portion includes treatment gas injectors.

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